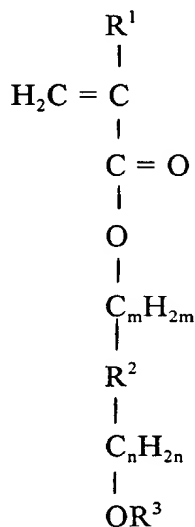


ABSTRACT OF DISCLOSURE

Monomers expressed by the following general formula are polymerized so as to obtain polymer, and the polymer and photoacid generator is dissolved in solvent so as to form a chemically amplified resist layer large in both transparency and sensitivity to ArF excimer laser light and improved in resolution.



ps wherein R¹ represents a hydrogen atom or a methyl group, R² represents a bridged hydrocarbon group having the carbon number between 7 and 22, m equals 0 or 1, n equals 0 or 1 and R³ represents a hydrogen atom, a methyl group or an acetyl group.